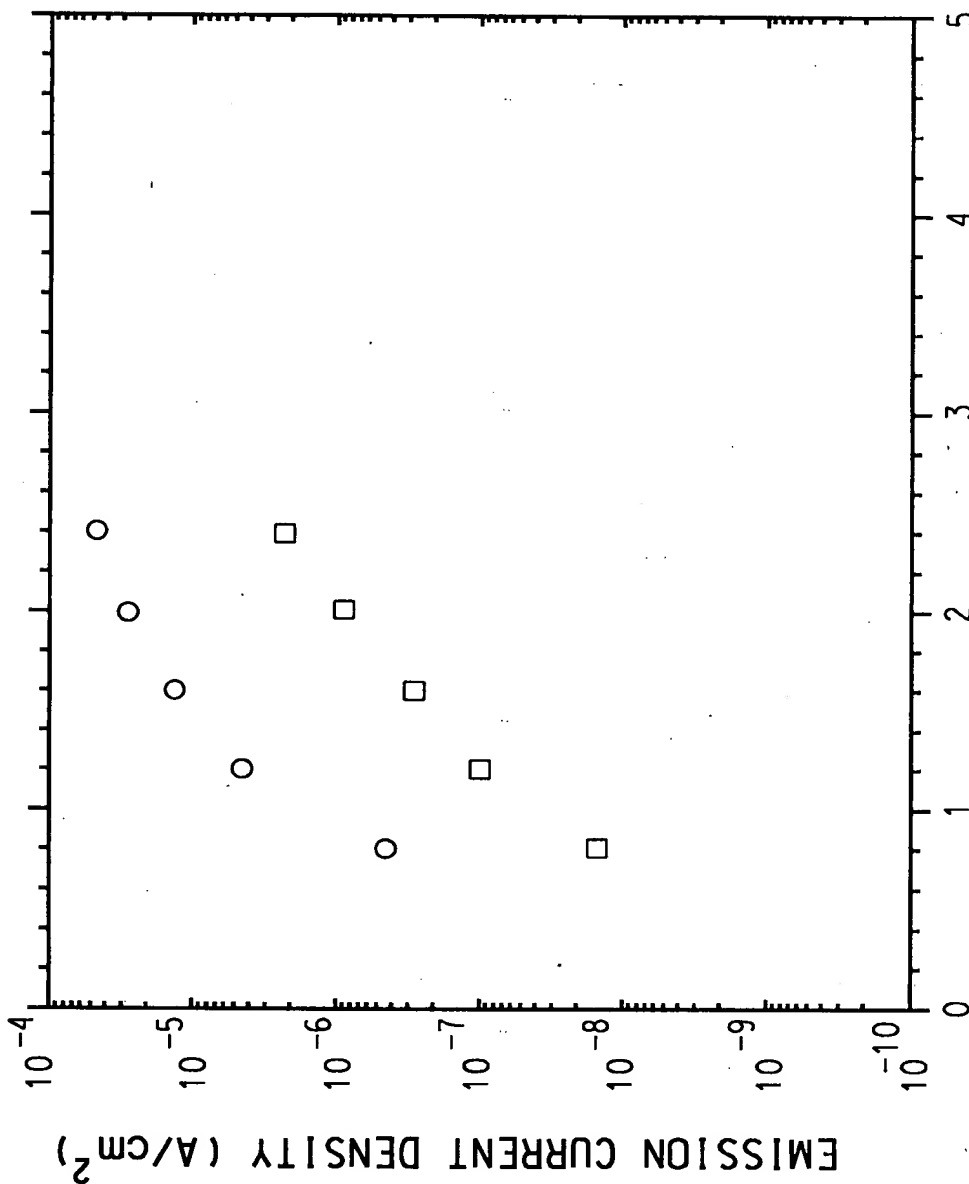


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○ After Process
□ As Fired



ELECTRIC FIELD ($V/\mu m$)

FIG. 1

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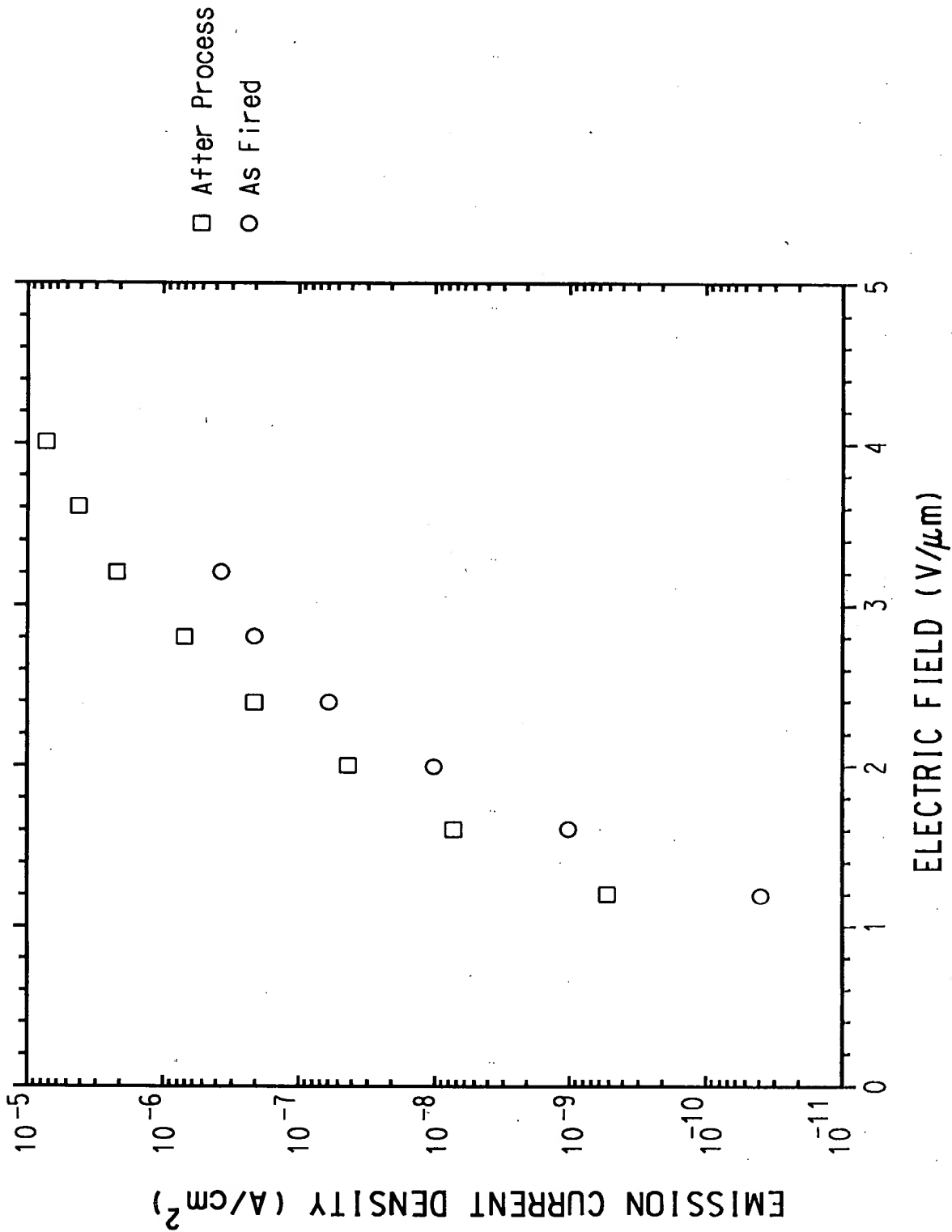


FIG. 2

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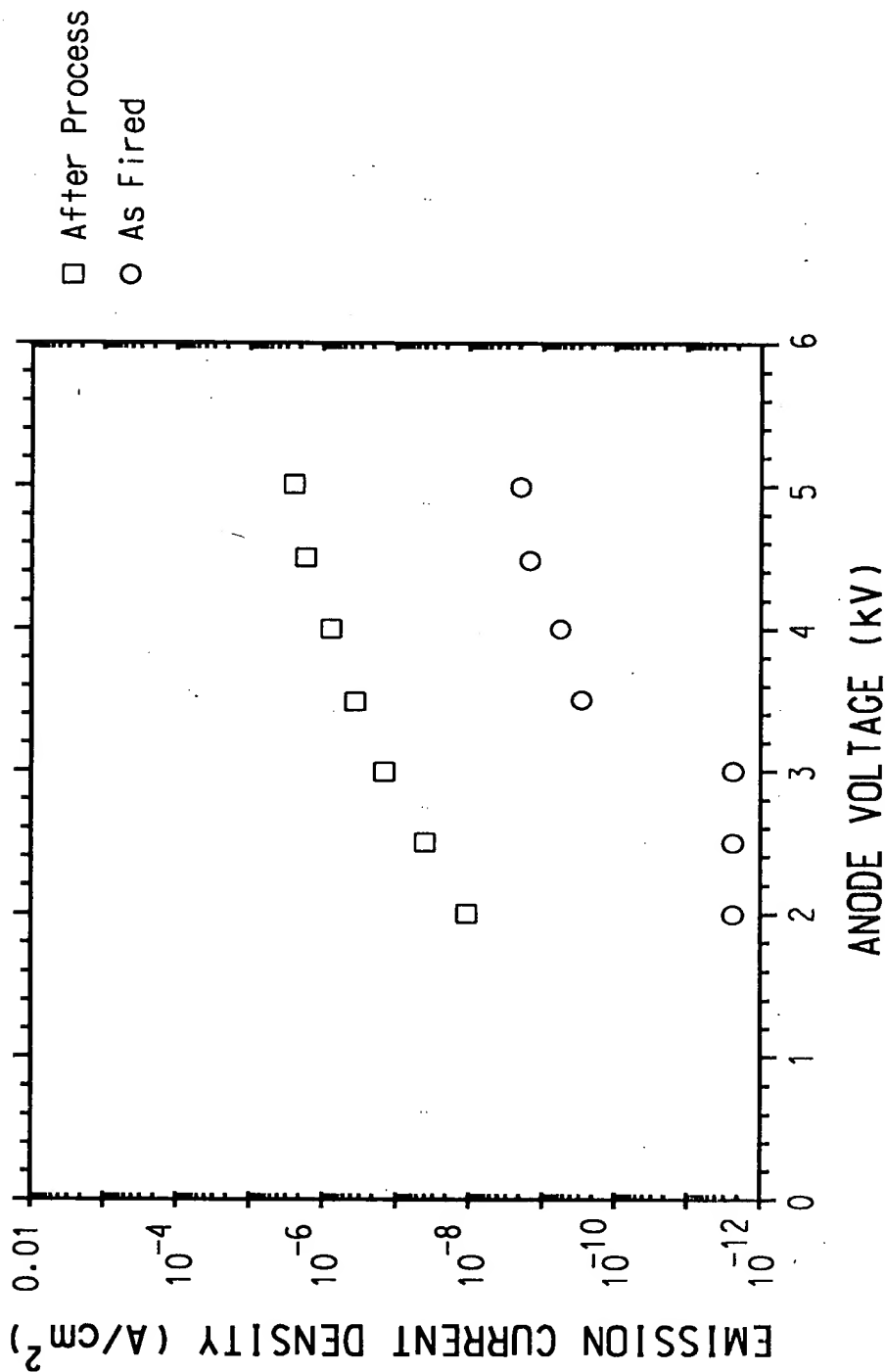


FIG. 3

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□ After Process
○ As Fired

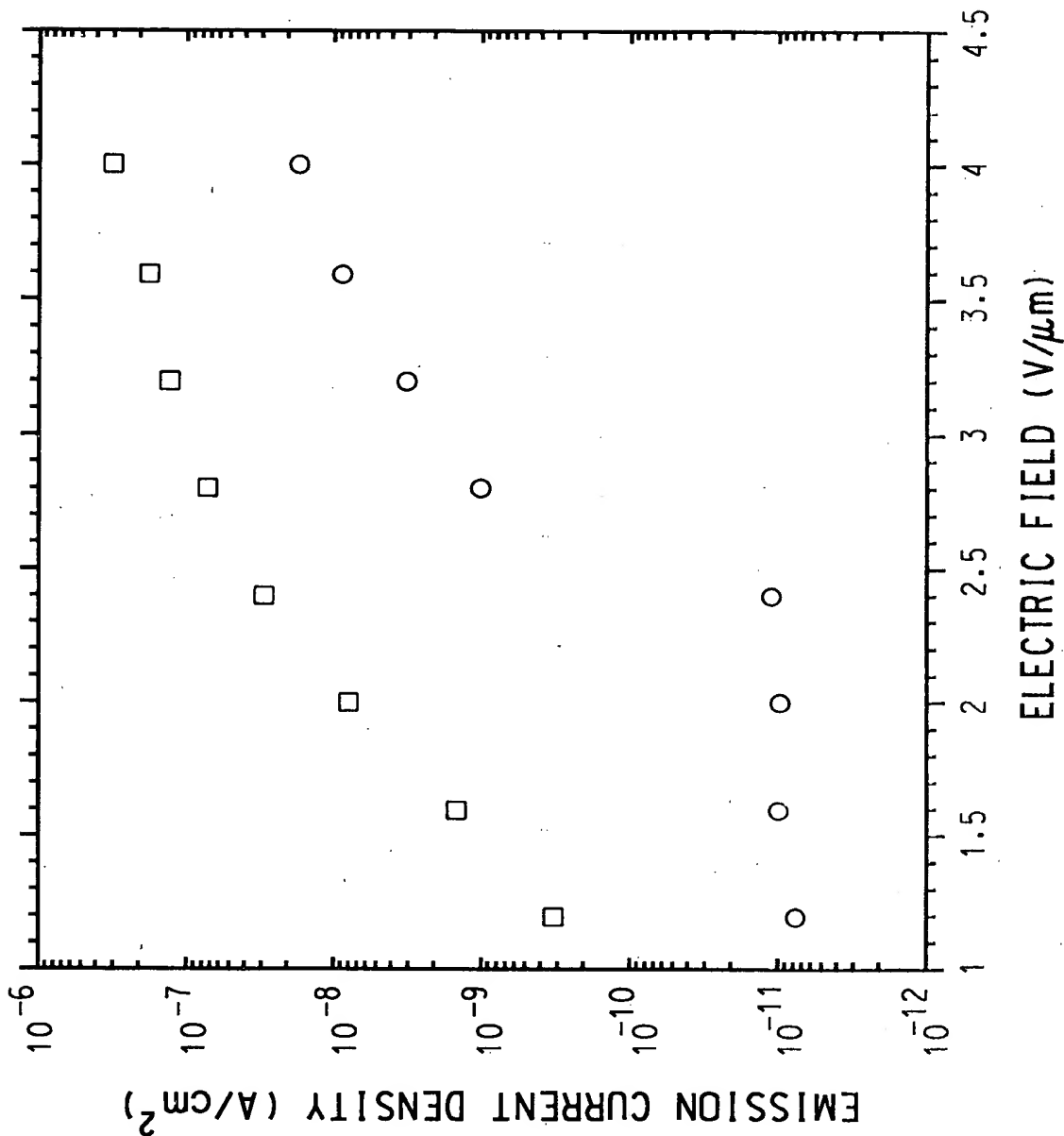
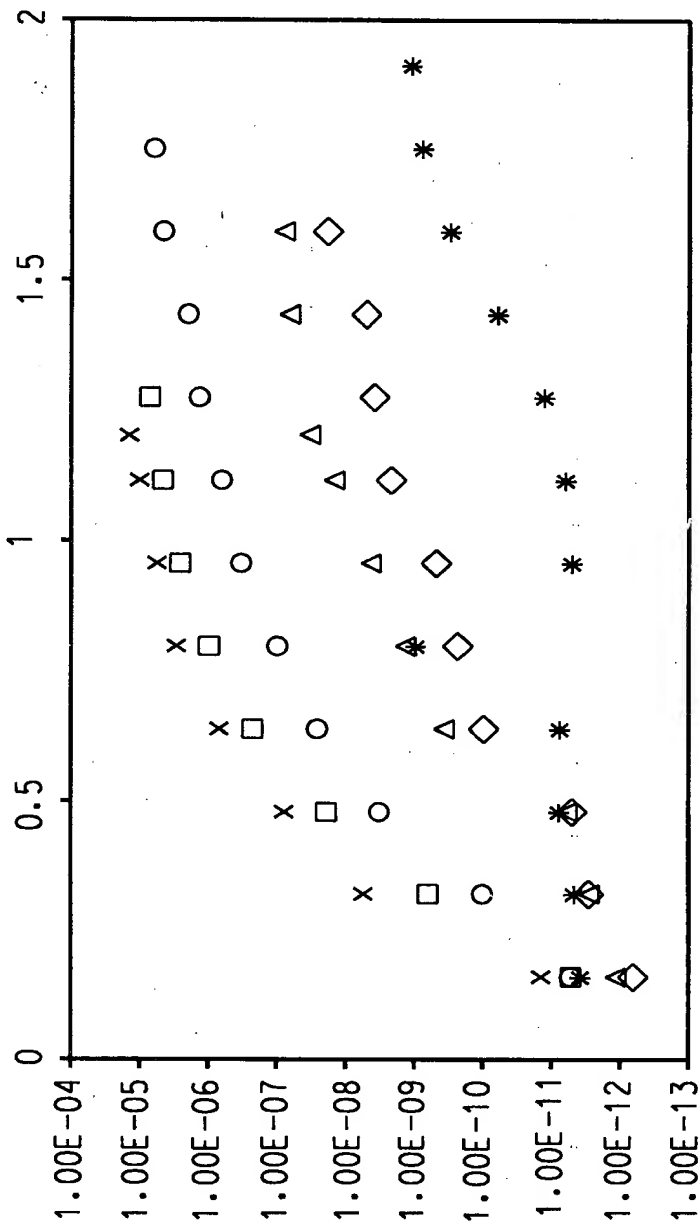


FIG. 4

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ELECTRIC FIELD (V/μm)

FIG. 5

- ◇ Example 9 - As fired
- Example 9 - After process
- Δ Example 10 - As fired
- x Example 10 - After process
- * Example 11 - As fired
- O Example 11 - After process

EMISSION CURRENT DENSITY (A/cm²)

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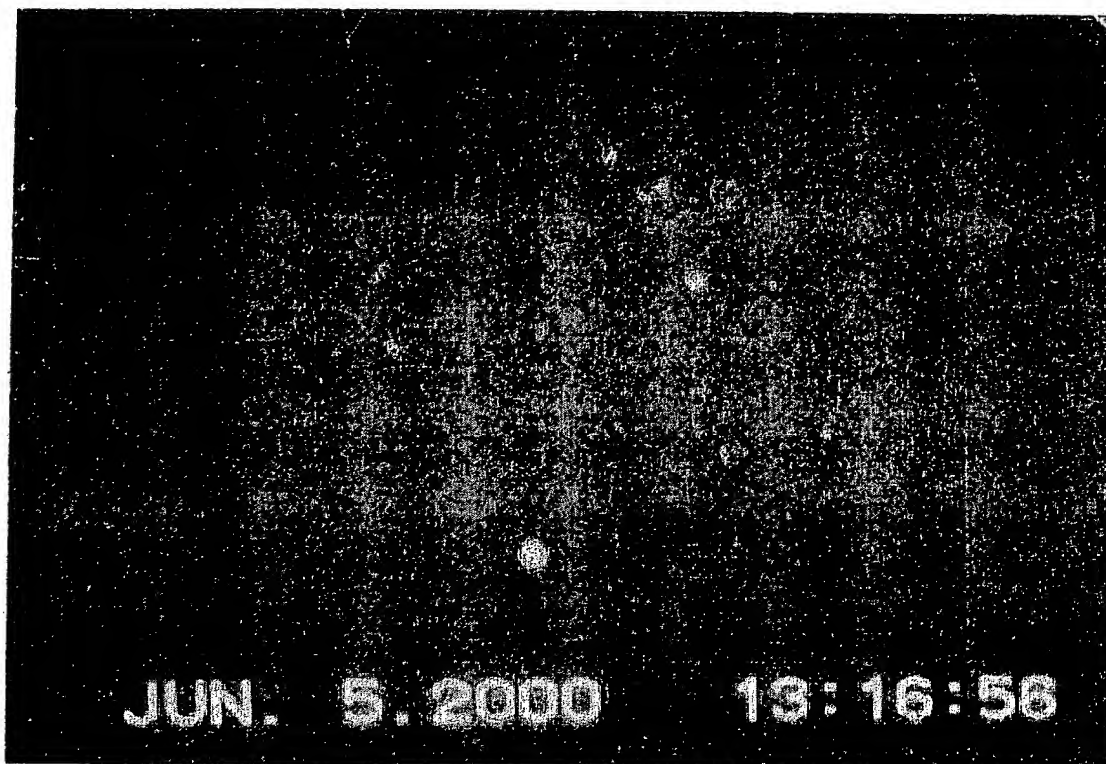


FIG. 6a

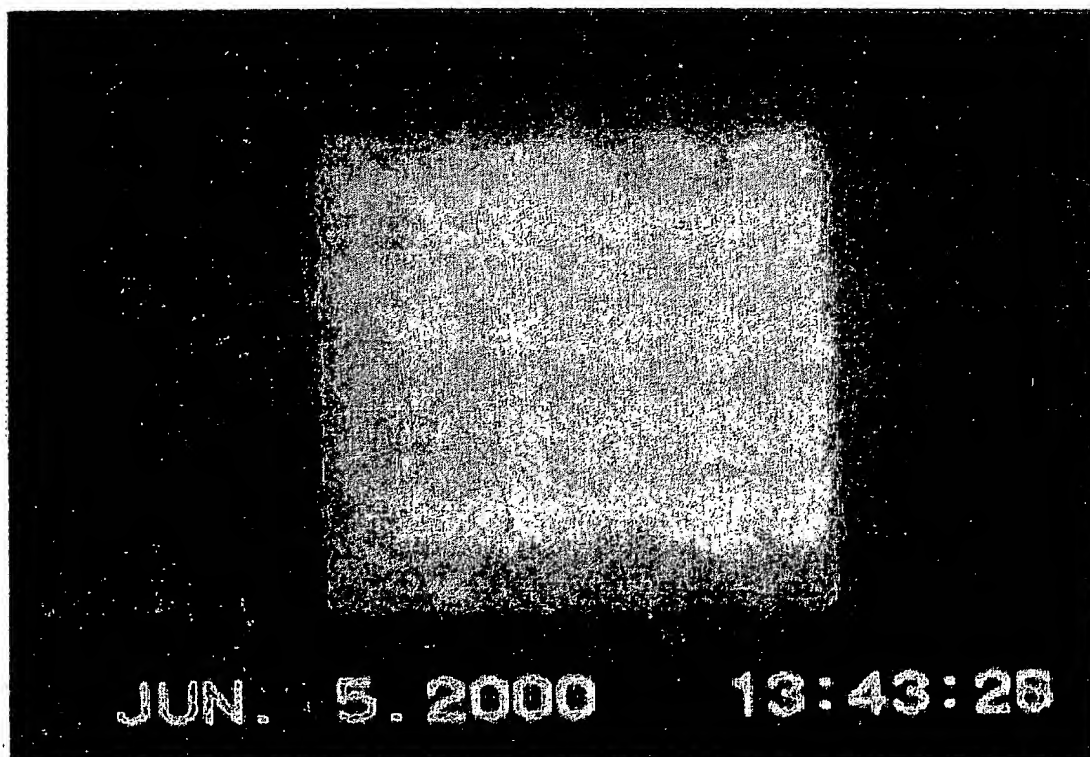


FIG. 6b

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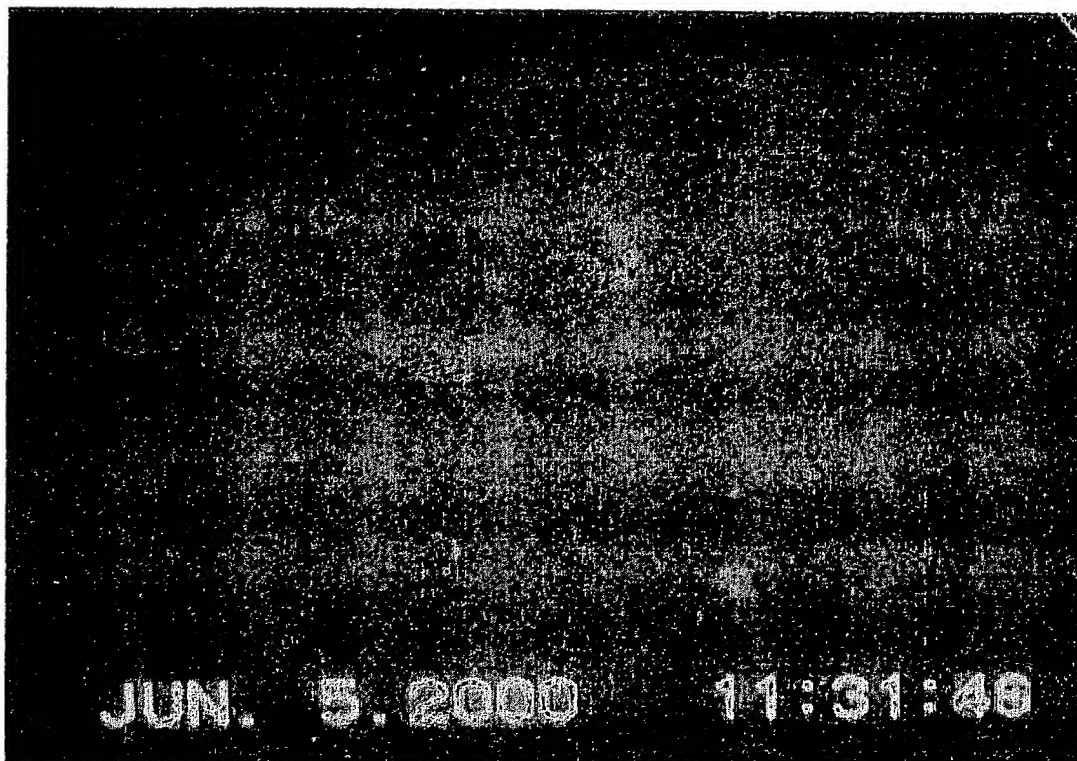


FIG. 6c

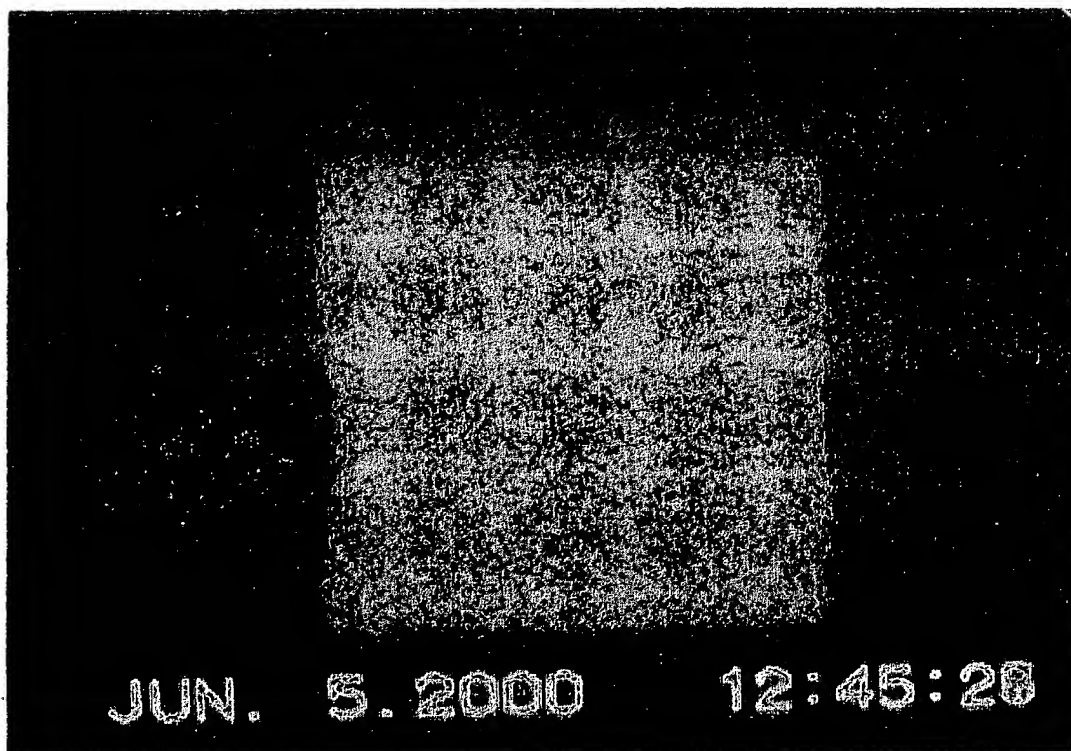


FIG. 6d

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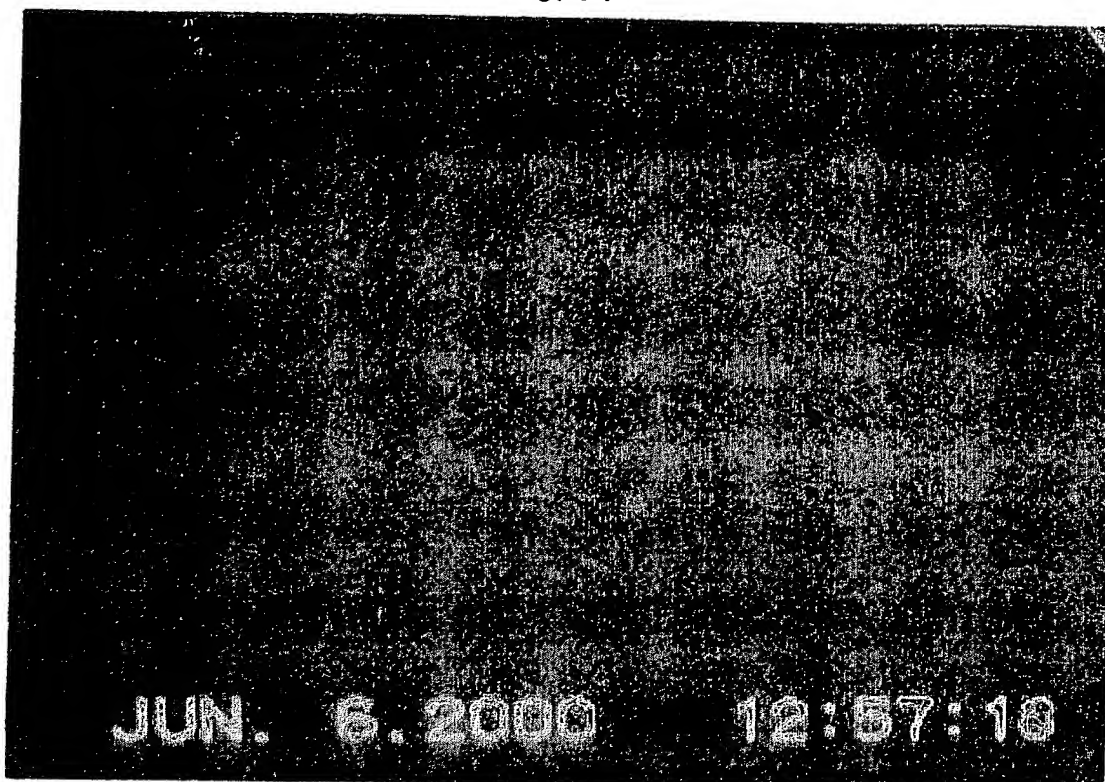


FIG. 6e

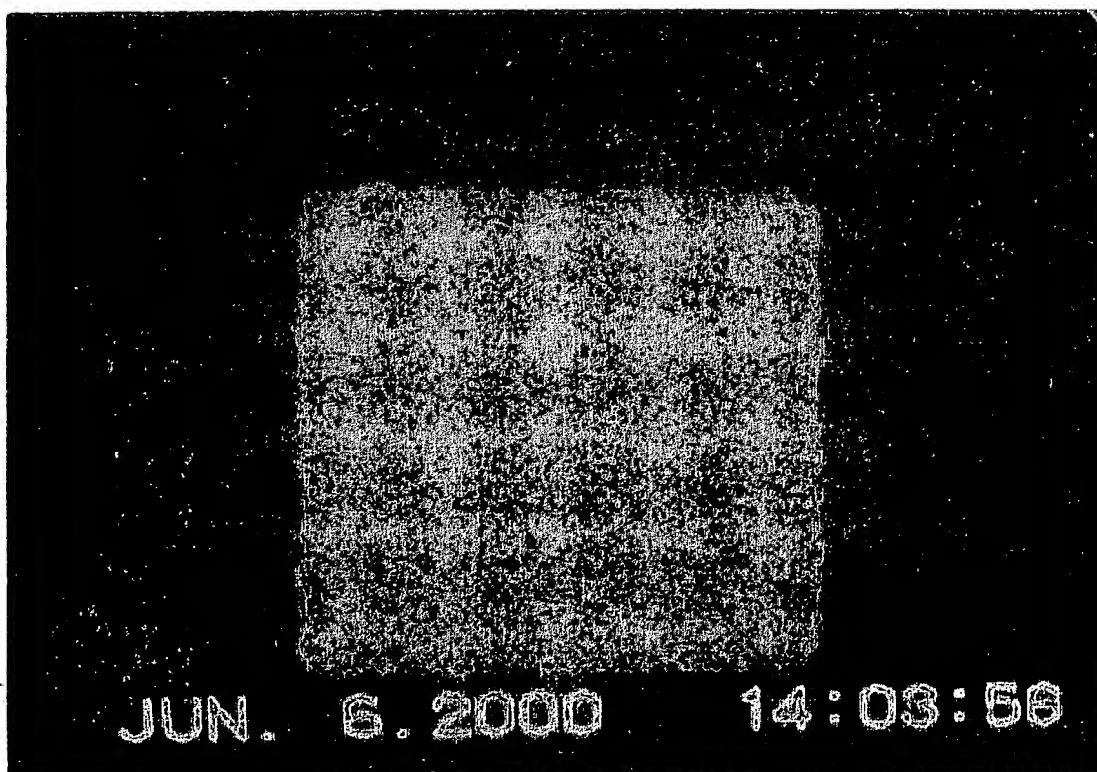


FIG. 6f

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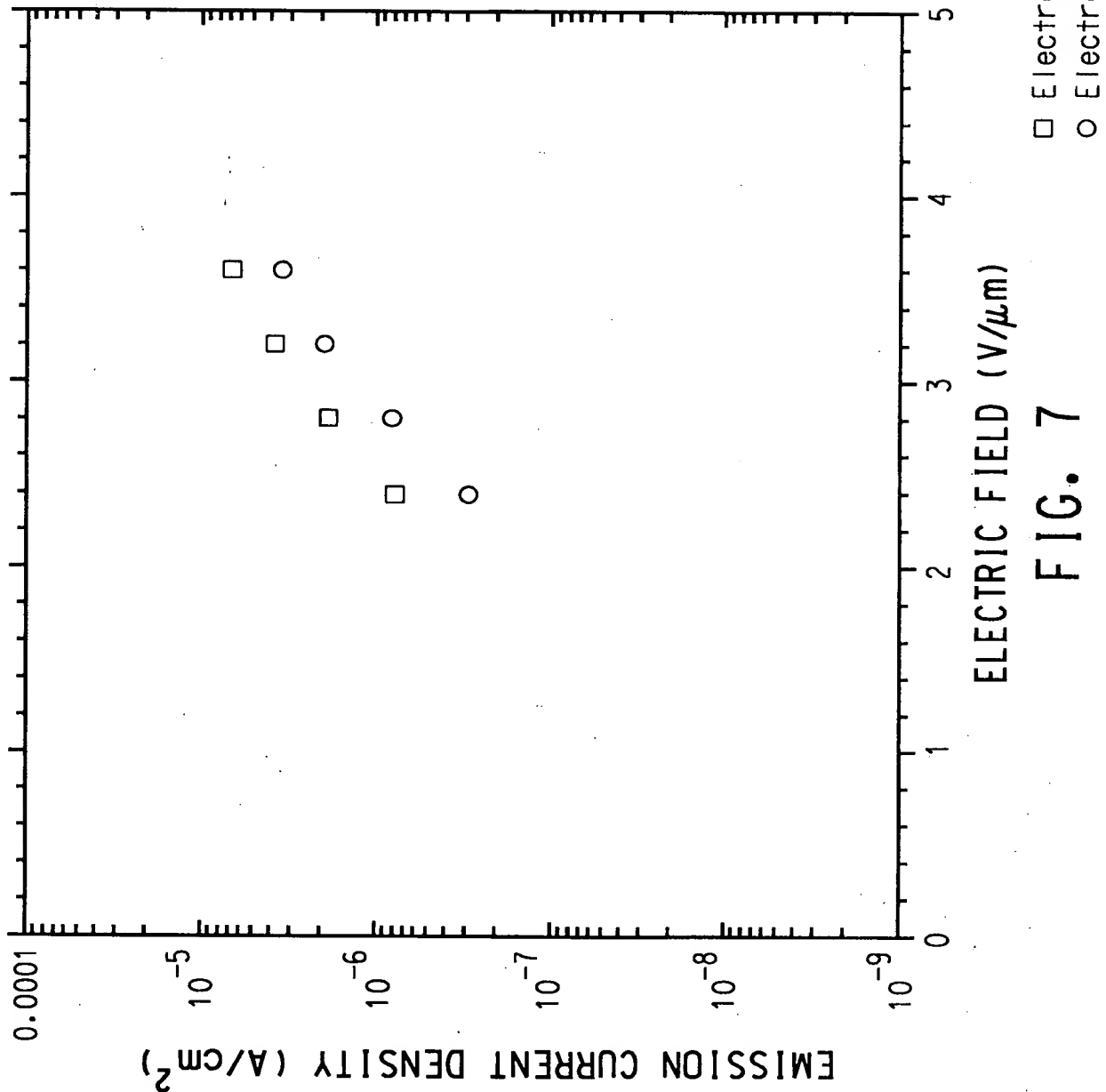


FIG. 7

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FIG. 8a

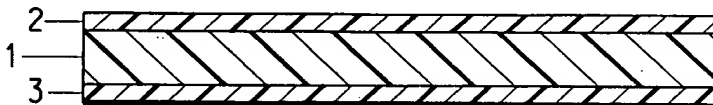


FIG. 8b

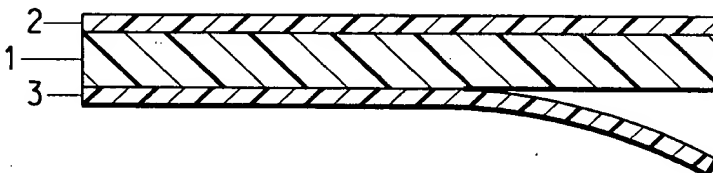


FIG. 8c

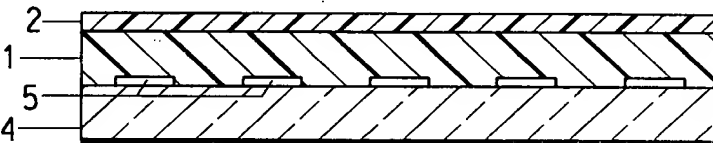


FIG. 8d

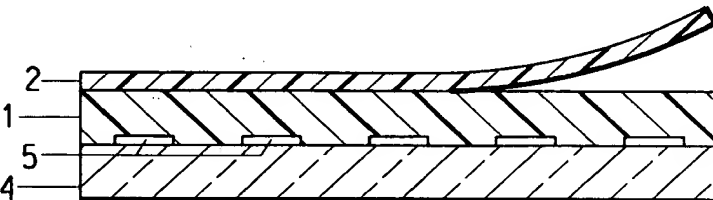


FIG. 8e

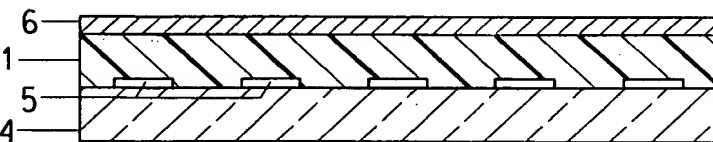
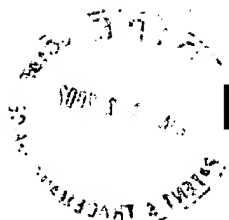


FIG. 8e



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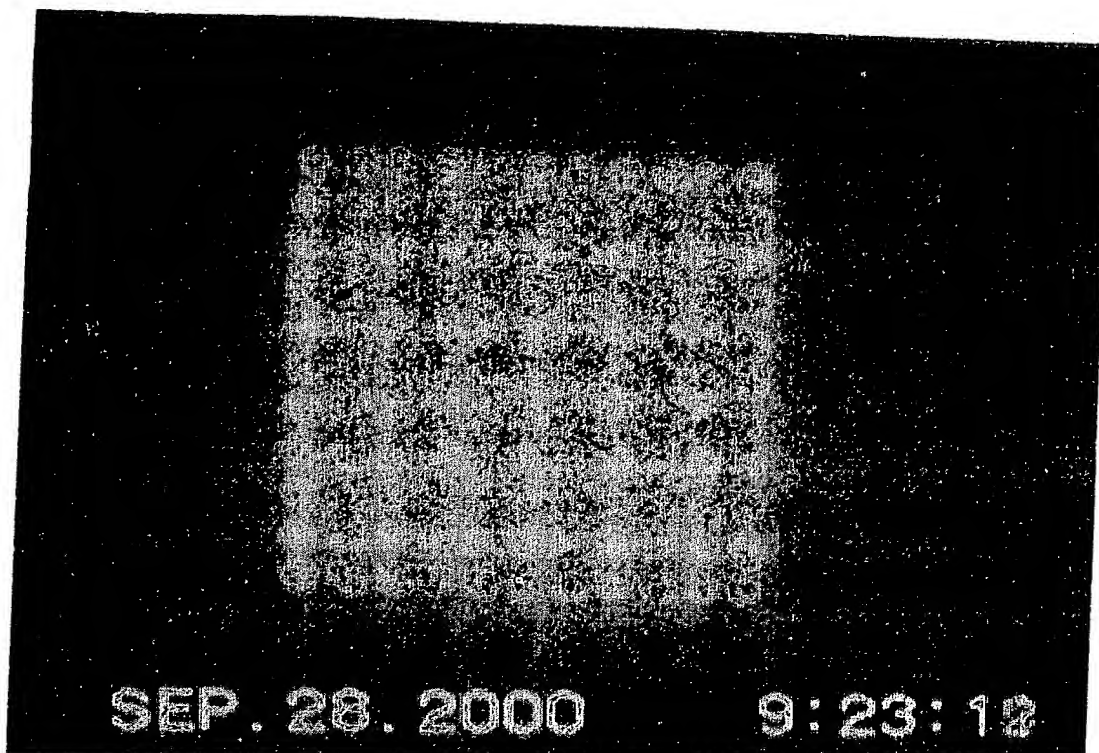


FIG. 9a

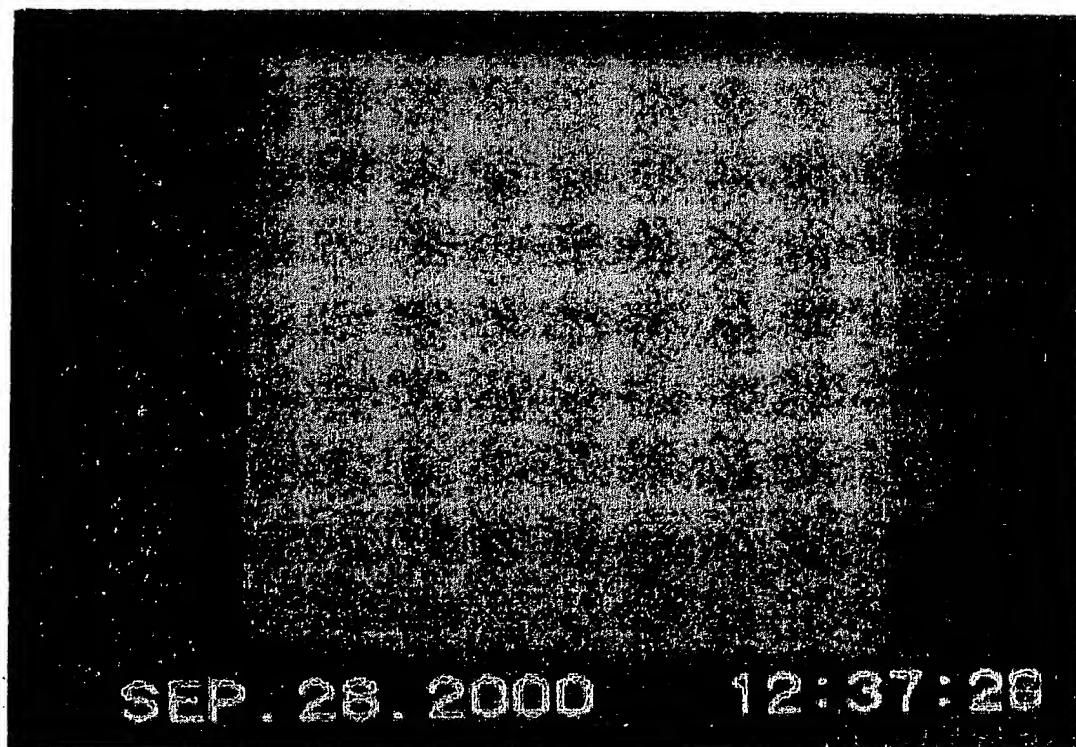


FIG. 9b

09882719.010202

SEP 28 2000
E.I. DU PONT DE NEMOURS

Docket No: 673
Title: Process for Improving The Emission Of Electron Field
Inventor: Joseph Bouchard, et. al.
Appl. No.: 682,719
E. I. DuPont de Nemours

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FIG. 10



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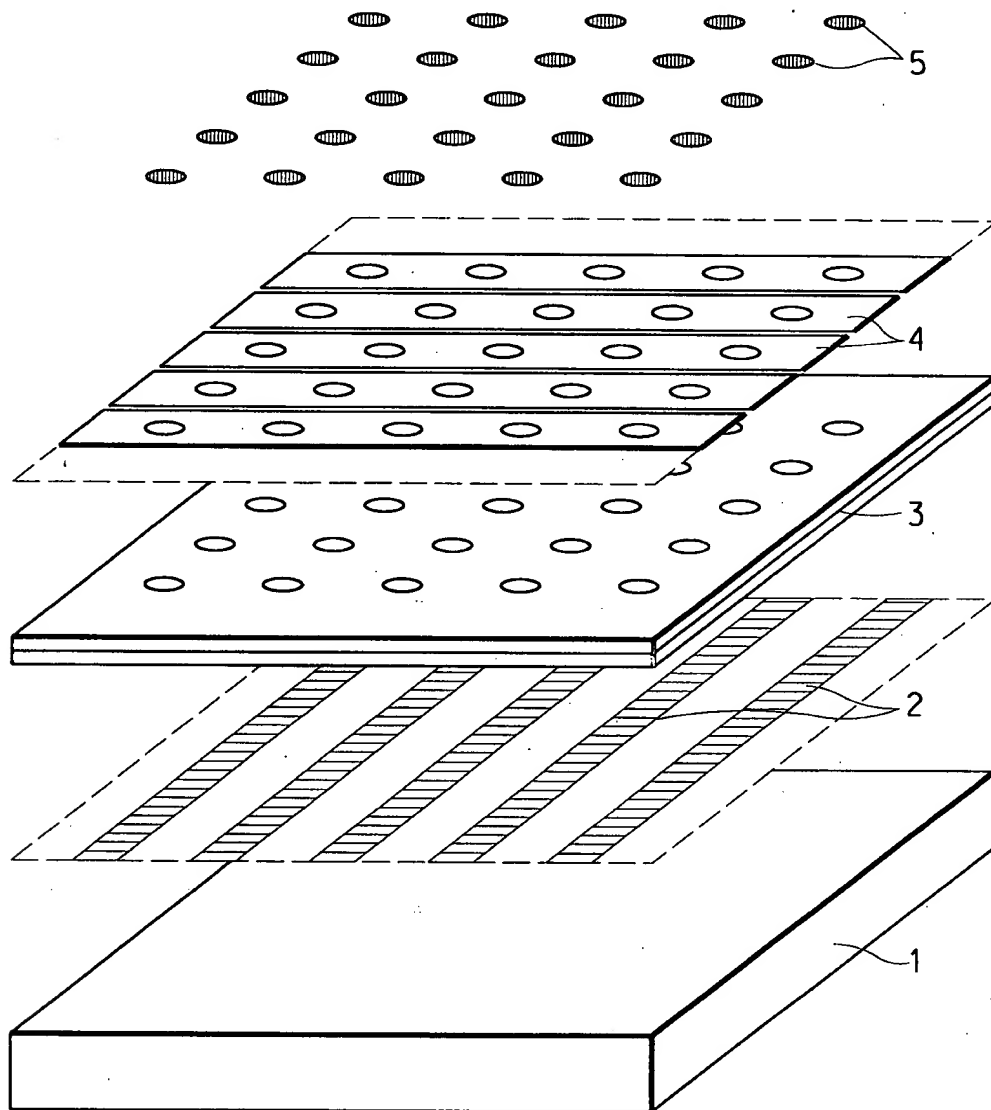


FIG. 11a

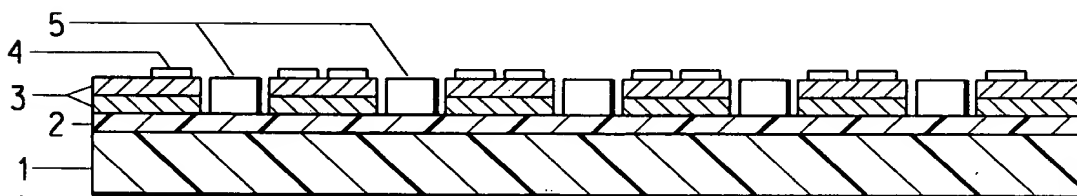


FIG 11b

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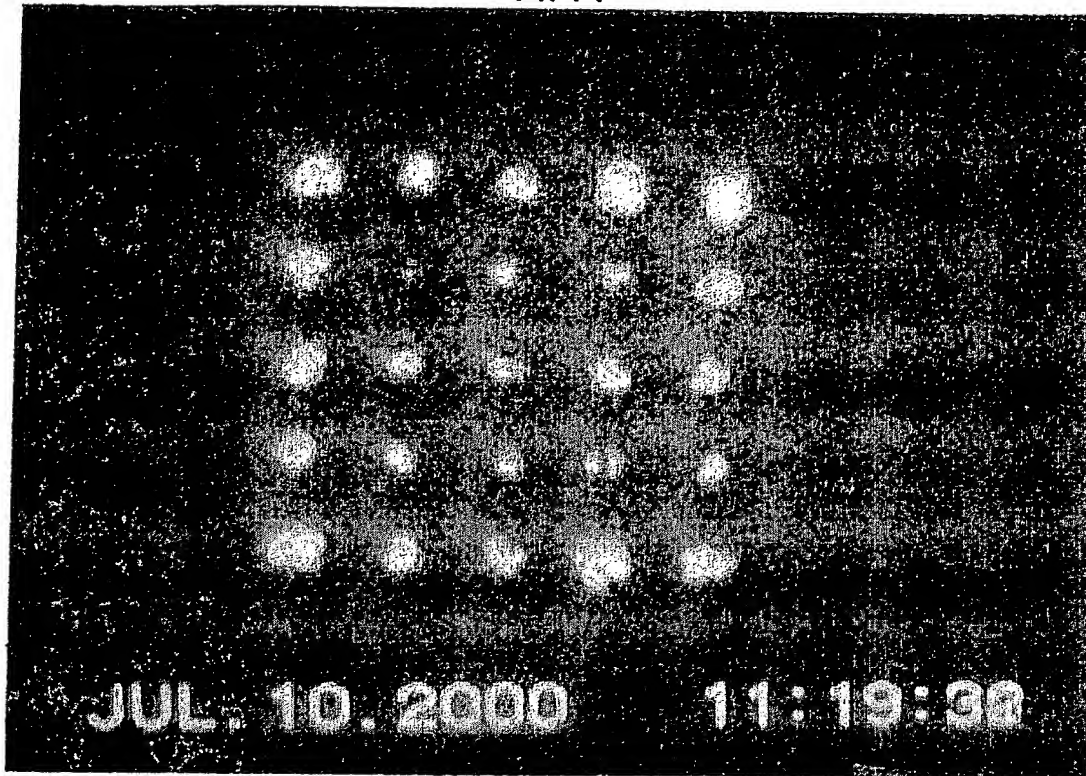


FIG. 12a

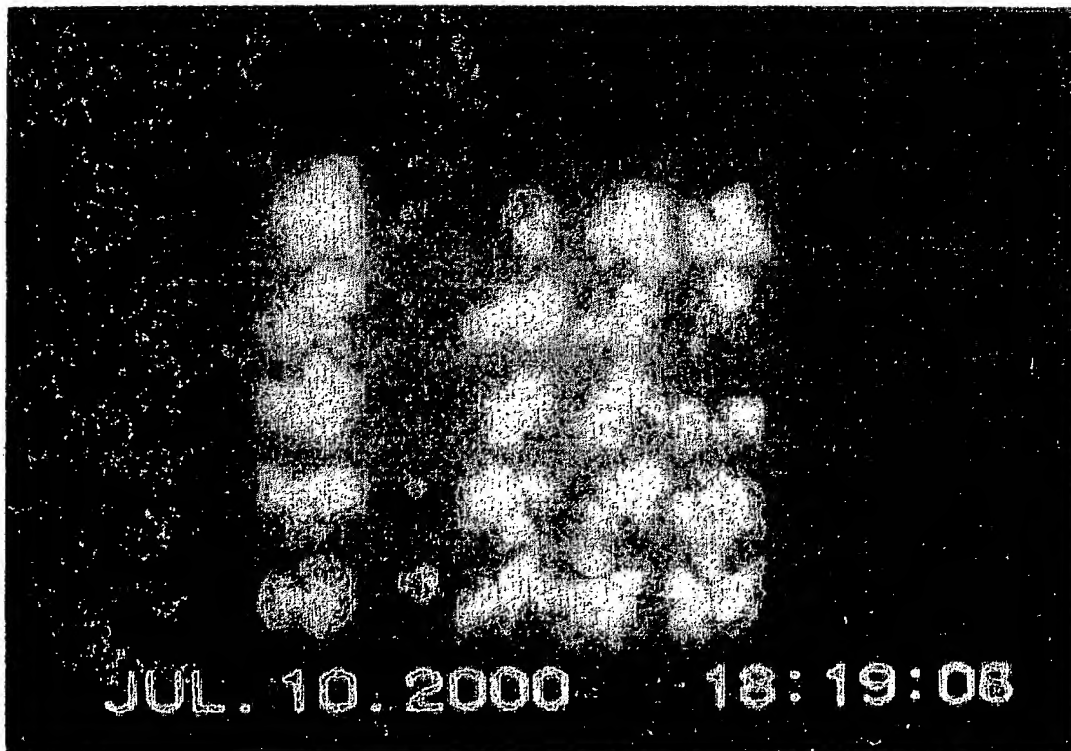


FIG. 12b

202010"6T28860